AMENDMENTS TO THE CLAIMS:

The following listing of claims replaces all prior listings, and all prior versions, of claims in the application.

LISTING OF CLAIMS:

- (Currently amended) A decorative material comprising at least a 1. substrate, a low-luster pattern ink layer-partially formed on a part of the substrate, leaving a part of the substrate on which the low-luster pattern ink layer is not formed, and a surface protective layer which is present on and in direct contact with the lowluster pattern ink layer so as to cover a whole surface including both a region where the low-luster pattern ink layer is formed and a region where no low-luster pattern ink layer is formed, wherein the surface protective layer is formed by crosslinking and curing an ionizing radiation-curable resin composition, and provided therein with a first, low-gloss region which is located in a first portion of the surface protective layer just above the low-luster pattern ink layer and in the vicinity of the first portion, and with a second region, located in the surface protective layer in a second portion other than the first portion and the vicinity of the first portion, the first, low-gloss region having a lower gloss than the second region, the low-luster pattern ink layer serving to generate a difference in gloss between the first and second regions, the first, lowgloss region being visually recognized as a concave portion, the low-luster pattern ink layer being formed of a low-luster pattern ink having a property of interacting with the ionizing radiation-curable resin composition to cause elution, dispersion and mixing therebetween.
- 2. (Currently amended) A decorative material comprising at least a substrate, a <u>low-luster</u> pattern ink layer-partially formed on <u>part of</u> the substrate,

leaving a part of the substrate on which the low-luster pattern ink layer is not formed, and a surface protective layer which is present on and in direct contact with the low-luster pattern ink layer so as to cover a whole surface including both a region where the low-luster pattern ink layer is formed and a region where no low-luster pattern ink layer is formed, the low-luster pattern ink layer serving to generate a difference in gloss between the region where the low-luster pattern ink layer is formed and the region where no low-luster pattern ink layer is formed, wherein the surface protective layer is formed by crosslinking and curing an ionizing radiation-curable resin composition, and a low-luster pattern ink forming the low-luster pattern ink layer contains a non-crosslinked urethane resin as a binder and the ionizing radiation-curable resin composition contains a (meth)acrylate monomer, and the low-luster pattern ink having a property of interacting with the ionizing radiation-curable resin composition to cause elution, dispersion and mixing therebetween.

- 3. (Currently amended) The decorative material according to claim 2, wherein the <u>low-luster</u> pattern ink forming the <u>low-luster</u> pattern ink layer contains the non-crosslinked urethane resin and an unsaturated polyester resin as a binder.
- 4. (Previously presented) The decorative material according to claim 2, wherein the ionizing radiation-curable resin composition contains a (meth)acrylate monomer solely.
- (Currently amended) The decorative material according to claim 1, wherein the <u>low-luster</u> pattern ink forming the <u>low-luster</u> pattern ink layer has an uneven thickness.

- 6. (Currently amended) The decorative material according to claim 5, wherein the <u>low-luster</u> pattern ink layer has a first <u>sub-layerfilm region</u> and a second <u>sub-layerfilm region</u> having a relatively small thickness as compared to the thickness of the first <u>sub-layerfilm region</u>, and a portion just above and in the vicinity of the first <u>sub-layerfilm region</u> is a first sub-region, whereas a portion just above and in the vicinity of the second <u>sub-layerfilm region</u> is a second sub-region—region having a relatively high gloss as compared to that of the first sub-region.
- 7. (Currently amended) The decorative material according to claim 1, wherein the surface protective layer contains fine particles, and an average particle size of the fine particles is larger than close to a plus side value of a maximum thickness of the surface protective layer located just above the low-luster pattern ink layer such that the fine particles are protruded on the surface of the surface protective layer above the low-luster pattern ink layer.
- 8. (Original) The decorative material according to claim 7, wherein a coefficient of variation (CV value) of a particle size distribution of the fine particles which is represented by the formula: [(standard deviation of particle size/average particle size) x 100] is 30% or lower.
- 9. (Currently amended) The decorative material according to claim 7, wherein the fine particles satisfy a relationship represented by the following formula (I):

1.05 x
$$t_M \le d_A \le t_G$$
 (I)

wherein d_A is an average particle size of the fine particles; t_M is a maximum thickness of the surface protective layer located just above the <u>low-luster</u> pattern ink layer; and t_G is a thickness of the surface protective layer located in a region where no <u>low-luster</u> pattern ink layer is formed.

- 10. (Previously presented) The decorative material according to claim 7, wherein the surface protective layer contains the fine particles in an amount of 2 to 20% by mass.
- 11. (Previously presented) The decorative material according to claim 1, wherein the surface protective layer is formed by crosslinking and curing the ionizing radiation-curable resin composition containing an ethylene oxide-modified polymerizable compound, and contains particles of baked kaolin.
- 12. (Currently amended) The decorative material according to claim 1, wherein the <u>low-luster</u> pattern ink forming the <u>low-luster</u> pattern ink layer contains an extender pigment.
- 13. (Previously presented) The decorative material according to claim 1, wherein the ionizing radiation-curable resin composition is an electron beam-curable resin composition.
- 14. (Currently amended) The decorative material according to claim 1, wherein a surface of the surface protective layer located above the first, low-gloss region has a convex shape.

- 15. (Currently amended) The decorative material according to claim 1, further comprising a penetration-preventing layer formed between the substrate and the <u>low-luster</u> pattern ink layer.
- 16. (Original) The decorative material according to claim 15, wherein the substrate is a penetrable substrate.
- 17. (Currently amended) The decorative material according to claim 1, wherein a colored layer, a pattern layer and the penetration-preventing layer are successively laminated on the substrate, and the <u>low-luster</u> pattern ink layer as well as the surface protective layer which is present on and in direct contact with the <u>low-luster</u> pattern ink layer so as to cover a whole surface including both the region where the <u>low-luster</u> pattern ink layer is formed and the region where no <u>low-luster</u> pattern ink layer is formed on the laminated layers.
- 18. (Currently amended) The decorative material according to claim 17, wherein the pattern layer has a woodgrain pattern, and the <u>low-luster</u> pattern ink layer forms a <u>low-gloss</u> region corresponding to vessels of the woodgrain pattern.
- 19. (Previously presented) A decorative plate comprising a substrate plate and the decorative material as defined in claim 1 which is attached onto the substrate plate.

- 20. (Currently amended) The decorative material according to claim 2, wherein the <u>low-luster</u> pattern ink forming the <u>low-luster</u> pattern ink layer has an uneven thickness.
- 21. (Currently amended) The decorative material according to claim 2, wherein the surface protective layer contains fine particles, and an average particle size of the fine particles is <u>larger than</u>close to a plus-side value of a maximum thickness of the surface protective layer located just above the <u>low-luster</u> pattern ink layer such that the fine particles are protruded on the surface of the surface protective layer above the low-luster pattern ink layer.
- 22. (Previously presented) The decorative material according to claim 2, wherein the surface protective layer is formed by crosslinking and curing the ionizing radiation-curable resin composition containing an ethylene oxide-modified polymerizable compound, and contains particles of baked kaolin.
- 23. (Currently amended) The decorative material according to claim 2, wherein the <u>low-luster</u> pattern ink forming the <u>low-luster</u> pattern ink layer contains an extender pigment.
- 24. (Previously presented) The decorative material according to claim 2, wherein the ionizing radiation-curable resin composition is an electron beam-curable resin composition.

- 25. (Currently amended) The decorative material according to claim 2, wherein a surface of the surface protective layer located above the <u>low-luster</u> pattern ink layer has a convex shape.
- 26. (Currently amended) The decorative material according to claim 2, further comprising a penetration-preventing layer formed between the substrate and the <u>low-luster</u> pattern ink layer.
- 27. (Currently amended) The decorative material according to claim 2, wherein a colored layer, a pattern layer and the penetration-preventing layer are successively laminated on the substrate, and the <u>low-luster</u> pattern ink layer as well as the surface protective layer which is present on and in direct contact with the low-luster pattern ink layer so as to cover a whole surface including both the region where the <u>low-luster</u> pattern ink layer is formed and the region where no <u>low-luster</u> pattern ink layer is formed on the laminated layers.
- 28. (Previously presented) A decorative plate comprising a substrate plate and the decorative material as defined in to claim 2 which is attached onto the substrate plate.
- 29. (New) The decorative material according to claim 1, wherein the low-luster pattern ink forming the low-luster pattern ink layer contains a non-crosslinked urethane resin.